

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 05-005988

(43)Date of publication of application : 14.01.1993

(51)Int.Cl.

G03F 7/028
G03F 7/00
G03F 7/004
G03F 7/004
G03F 7/004
G03F 7/027
G03F 7/029
H01L 21/027

(21)Application number : 03-152062

(71)Applicant : FUJI PHOTO FILM CO LTD

(22)Date of filing : 24.06.1991

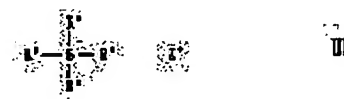
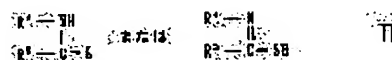
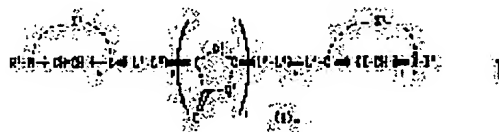
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(54) PHOTOPOLYMERIZABLE COMPOSITION

(57)Abstract:

PURPOSE: To obtain a photopolymerizable composition having high sensitivity against active ray in a wide region from ultraviolet ray to visible ray.

CONSTITUTION: This photochemical polymerizing composition contains at least one compound selected from a group consisting of: (i) polymerizable compound having an addition polymerizable unsaturated bond; (ii) a methine compound expressed in formula (I), (iii) a compound (a) having carbon-halogen bond, aromatic onium salt (b), an organic peroxide (c), a thiocompound (d) expressed in formula (II), hexaaryl biimidazole (e), a ketooxim ester (f) and a compound (g) expressed in formula (III).



LEGAL STATUS

[Date of request for examination]

15.03.1995

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or